Democratic elections judge.

Mrs. Hiteshew, an accomplished seamstress who stitched many christening gowns and First Communion dresses, did free alterations for those who could not afford to pay. She also loved the Orioles, classical music and reading.

A Mass of Christian burial was offered Friday at Our Lady of Victory Roman Catholic Church in Arbutus, where Mrs. Hiteshew was a parishioner.

In addition to her son, she is survived by eight other sons, William Dorsey Hiteshew Jr. of Joppa, F. Donald Hiteshew of Baytown, Texas, Milton D. Hiteshew of Pasadena, John D. Hiteshew of Catonsville, Stephen C. Hiteshew of Phoenix, Ariz., Herbert F. Hiteshew of Baltimore, and Charles E. Hiteshew and Walter C. Hiteshew, both of Ellicott City; a daughter, H. Louise Lawson of Ellicott City; 35 grandchildren and 24 great-grandchildren.

Mrs. Hiteshew also was preceded in death by a daughter, Virginia A. Greenfield, and another son, Philip T. Hiteshew.

Copyright © 2006, The Baltimore Sun | Get Sun home delivery

☐ Talk about it ☐ E-mail it ☐ Print it ☐ Contact us

Top obituaries headlines

- Phyllis M. Chait, 87, homemaker and genealogist
- Robert Anthony Kelly Sr., 79, automobile salesman
- James F. McCadden, 64, pilot, law partner, licensed captain
- Frances C. Wierum, 103, homemaker and pianist
- Deaths elsewhere

Top baltimoresun.com headlines

- Lawmakers, BGE promise lower increases
- Tagliabue to retire as NFL's chief in July
- · Regents' lobby activity faulted
- Belarus election is declared invalid
- U.S. judge is asked to order housing for poor in suburbs

Most e-mailed in the past 24 hours

- 1. Millions face squeeze on mortgages
- 2. Fears for the farm life
- 3. Grocer a timely part of Shabbos tradition
- 4. Immigration bill draws criticism
- 5. Eileen Ambrose: Putting \$743 into perspective





Tropical Isla Maldives Islan Reunion Islan On www.trop



Tropical Isla Maldives Islan Reunion Islan

Cayman Isia Special Offe enter the Cayl Www.cayl

Bahamas Va Island, Nassa Acklins, Andr Search History

(HEATENS, INSPEC, JAPES, WPATEN)
3/29/05

=> d 18 1-4 abs,bib

ANSWER 1 OF 4 USPATFULL on STN AB With respect to a liquid phase growth method for a silicon crystal in which the silicon crystal is grown on a substrate by immersing the substrate in a solvent or allowing the substrate to contact the solvent, a gas containing a raw material and/or a dopant is supplied to the solvent after at least a part of the gas is decomposed by application of energy thereto. In this manner, a liquid phase growth method for a silicon crystal, the method capable of achieving continuous growth and suitable for mass production, a manufacturing method for a solar cell and a liquid phase growth apparatus for a silicon crystal are provided. CAS INDEXING IS AVAILABLE FOR THIS 2004:86293 USPATRULL AN Liquid phase growth hethod for ΤI silicon crystal manufacturing method for and liquid phase growth apparatus for silicon crystal Nishida, Shoji, Nara, JAPAN Yoshino Takehito, Nara, JAPAN Iwane Masaaki Nara (1997) IN Iwane, Masaaki, Nara APAN Mizutani, Masaki, Nara MATAN Tokyo, JAPAN (non-U.S. corporation) CANON KABUSHIKI KAISHA PA 20040408 ΡI US_2004065251 A US 2003-676094 20031002 (10) AI PRAI JP 2002 294897 20021008 DT Utility APPLICATION FS FITZPATRICK CELLA HARPER & SCINTO, 30 ROCKEFELLER PLAZA, NEW YORK, NY, LREP 10112 CLMN Number of Claims: 33 Exemplary Claim: 1 ECL DRWN 5 Drawing Page(s) LN.CNT 964 CAS INDEXING IS AVAILABLE FOR THIS PATENT. L8 ANSWER 2 OF 4 USPATFULL on STN AB Provided are a liquid phase growth method of silicon crystal comprising a step of injecting a source gas containing at least silicon atoms into a solvent to decompose the source gas and, simultaneously therewith, dissolving the silicon atoms into the solvent, thereby supplying the silicon atoms into the solvent, and a step of dipping or contacting a substrate into or with the solvent, thereby growing a silicon crystal on the substrate; and a method of producing a solar cell utilizing the aforementioned method. Also provided is a liquid phase growth apparatus of a silicon crystal comprising means for holding a solvent in which silicon atoms are dissolved, and means for dipping or contacting a substrate into or with the solvent, the apparatus further comprising means for injecting a source gas containing at least silicon atoms into the solvent. These provide a liquid phase growth method of a silicon crystal and a production method of a solar cell each having high volume productivity and permitting continuous growth.

```
2002:211323 USPATFULL
 AN
 TI
        Liquid phase growth method of
        silicon crystal, method of producing solar, cell, and
        liquid phase growth apparatus
 IN
        Nishida, Shoji, Kanagawa-ken, JAPAN
        Nakagawa, Katsumi, Kanagawa-ken, JAPAN
        Ukiyo, Noritaka, Kanagawa-ken, JAPAN
        <del>Iwane, Masaaki,</del> Kanagawa-ken, JAPAN
        US_2002112660
 ÞΙ
                           Al
                                 20020822
       US 2002-120357
 ΑI
                                 20020412 (10)
                           Al
        DIVISION OF SET. No. US 1998-208377, filed on 10 Dec 1998, GRANTED, Pat.
        No. US 6391108
 PRAI
        JP 1997-342709
                             19971212
 DT
        Utility
 FS
        APPLICATION
 LREP
        FITZPATRICK CELLA HARPER & SCINTO, 30 ROCKEFELLER PLAZA, NEW YORK, NY,
 CLMN
        Number of Claims: 31
 ECL
        Exemplary Claim: 1
        4 Drawing Page(s)
 DRWN
 LN.CNT 614
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.
      ANSWER 3 OF 4 USPATFULL on STN
 rs.
 AB
        Provided are a liquid phase growth method
        of silicon crystal comprising a step of injecting a
        source gas containing at least silicon atoms into a solvent to decompose
        the source gas and, simultaneously therewith, dissolving the silicon
        atoms into the solvent, thereby supplying the silicon atoms into the
        solvent, and a step of dipping or contacting a substrate into
        or with the solvent, thereby growing a silicon
        crystal on the substrate; and a method of producing a solar cell
        utilizing the aforementioned method. Also provided is a liquid
        phase growth apparatus of a silicon
        crystal comprising means for holding a solvent in which
        silicon atoms are dissolved, and means for dipping or contacting
        a substrate into or with the solvent, the apparatus
        further comprising means for injecting a source gas containing at least
        silicon atoms into the solvent. These provide a liquid
        phase growth method of a silicon
        crystal and a production method of a solar cell each having high
        volume productivity and permitting continuous growth.
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.
 .AN
        2002:10790 USPATFULL
 TI
        LIQUID PHASE GROWTH METHOD OF
        SILICON CRYSTAL, METHOD OF PRODUCING SOLAR CELL, AND
        LIQUID PHASE GROWTH APPARATUS
 IN
        NISHIDA, SHOJI, HIRATSUKA-SHI, JAPAN
        NAKAGAWA, KATSUMI, ATSUGI-SHI, JAPAN
        UKIYO, NORITAKA, ATSUGI-SHI, JAPAN
        IWANE, MASAAKI, ATSUGI-SHI, JAPAN
 ΡI
        US_2002005158
                            A1
                                 20020117
        US 6391108
                            B2
                                 20020521
✓ AI
        US 1998-208377
                            A1
                                 19981210 (9)
 PRAI
        JP 1997-342709
                             19971212
 DT
        Utility
 FS
        APPLICATION
 LREP
        FITZPATRICK CELLA HARPER & SCINTO, 30 ROCKEFELLER PLAZA, NEW YORK, NY,
        10112
 CLMN
        Number of Claims: 31
        Exemplary Claim: 1
 ECL
 DRWN
        4 Drawing Page(s)
```

```
LN.CNT 614
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L8 ANSWER 4 OF 4 USPAT2 on STN
AB Provided are a liquid phase growth method of silicon crystal comprising a step of in source gas containing at least silicon atc
```

of silicon crystal comprising a step of injecting a source gas containing at least silicon atoms into a solvent to decompose the source gas and, simultaneously therewith, dissolving the silicon atoms into the solvent, thereby supplying the silicon atoms into the solvent, and a step of dipping or contacting a substrate into or with the solvent, thereby growing a silicon crystal on the substrate; and a method of producing a solar cell utilizing the aforementioned method. Also provided is a liquid phase growth apparatus of a silicon crystal comprising means for holding a solvent in which silicon atoms are dissolved, and means for dipping or contacting a substrate into or with the solvent, the apparatus further comprising means for injecting a source gas containing at least silicon atoms into the solvent. These provide a liquid phase growth method of a silicon crystal and a production method of a solar cell each having high

```
crystal and a production method of a solar cell each having high
       volume productivity and permitting continuous growth.
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
       2002:10790 USPAT2
AN
ΤI
       Liquid phase growth method of
       silicon crystal, method of producing solar cell, and
       liquid phase growth apparatus
       Nishida, Shoji, Hiratsuka, JAPAN
IN
       Nakagawa, Katsumi, Atsugi, JAPAN
       Ukiyo, Noritaka, Atsugi, JAPAN
       Iwane, Masaaki, Atsugi, JAPAN
       Canon Kabushiki Kaisha, Tokyo, JAPAN (non-U.S. corporation)
PA
     US 6391108
ΡI
                          B2
                               20020521
       US 1998-208377
                               19981210 (9)
ΑI
       JP 1997-342709
                           19971212
PRAI
DT
       Utility
FS
       GRANTED
       Primary Examiner: Utech, Benjamin L.; Assistant Examiner: Anderson,
EXNAM
       Matthew
       Fitzpatrick, Cella, Harper & Scinto
LREP
       Number of Claims: 18
CLMN
ECL
       Exemplary Claim: 1
DRWN
       4 Drawing Figure(s); 4 Drawing Page(s)
LN.CNT 552
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
=> d his
     (FILE 'HOME' ENTERED AT 13:31:15 ON 29 MAR 2005)
     FILE 'HCAPLUS, INSPEC, JAPIO, INPADOC, USPATFULL, USPAT2' ENTERED AT
     13:31:58 ON 29 MAR 2005
          27937 S (LPE OR LIQUID(W) PHASE(W) EPITAX? OR LIQUID(W) PHASE(W) GROW?)
Ll
L2
         193444 S (SI OR SILICON) (8A) (CRYSTAL?)
```

```
FILE 'HCAPLUS, INSPEC, JAPIO, INPADOC, USPATFULL, USPAT2' ENTERED AT 13:31:58 ON 29 MAR 2005

L1 27937 S (LPE OR LIQUID(W)PHASE(W)EPITAX? OR LIQUID(W)PHASE(W)GROW?

L2 193444 S (SI OR SILICON)(8A)(CRYSTAL?)

L3 114745 S (SUBSTRATE#)(6A)(SOLVENT# OR LIQUID#)

L4 178185 S (DOPANT#)

L5 21222 S (DECOMPOSIT?(4A)GAS?)

L6 338325 S (RAW(W)MATERIAL#)

L7 4630569 S (METAL#)

L8 4 S L1 AND L2 AND L3 AND L4 AND L5 AND L6 AND L7
```